35

## **CLAIMS**

## What is claimed is:

- A glass composition comprising, in mol%, 1-10% MO where M is selected from Ba, Sr, Ca and mixtures thereof, 5-30% MgO, 0.3-5%
   CuO, 0-2.5% P<sub>2</sub>O<sub>5</sub>, 0-2.5% ZrO<sub>2</sub>, 24-45% ZnO, 2-10% Al<sub>2</sub>O<sub>3</sub>, 35-50% SiO<sub>2</sub> and 0.1-3% A<sub>2</sub>O where A is selected from the group of alkali elements and mixtures thereof.
- A thick film composition comprising a dispersion of finely
   divided solids comprising:
  - (a) glass composition as in Claim 1; and
  - (b) organic medium.
- 3. The thick film composition of Claim 2 further comprising to ceramic filler.
  - 4. The thick film composition of Claim 3 wherein said ceramic filler comprises up to 17 wt. % of the total composition.
- 5. The thick film composition as in any one of Claims 2, 3, or 4, wherein said glass composition comprises 43-85 wt. % of the total composition.
- 6. The thick film composition as in any one of Claims 2, 3, or 4, wherein said organic medium comprises 15-40 wt. % of the total composition.
- The thick film composition of Claim 2 wherein the ceramic filler is selected from Al<sub>2</sub>O<sub>3</sub>, ZrO<sub>2</sub>, SiO<sub>2</sub>, TiO<sub>2</sub>, BaTiO<sub>3</sub>, cordierite, mullite, and mixtures thereof.
  - 8. A method of forming a multilayer circuit comprising the steps:
    - (a) providing an Aluminum nitride substrate;
    - (b) depositing the composition of any one of Claims 2-7 on said substrate;
    - (c) firing said composition and substrate forming an aluminum nitride article;
    - (d) providing a metallic conductive composition;

- (e) depositing said conductive composition on said aluminum nitride article; and
- (f) firing said aluminum nitrate article and said conductive composition.

5

- 9. A multilayer circuit formed by the method of Claim 8.
- 10. An article comprising the thick film composition of any one of Claims 2-7, wherein said thick film composition is processed to volatilize
  the organic polymeric binder and sinter the glass composition.
  - 11. A multilayer circuit comprising a plurality of internal thick film metallic conductive composition layers separated by layers of the thick film composition of any one of Claims 2-7, wherein the thick film composition is processed to volatilize the organic polymeric binder and sinter the glass composition.
  - 12. The multilayer circuit of any one of Claims 9 or 11, wherein said metallic conductive composition comprises Ag.

20

15

- 13. The multilayer circuit of any one of Claims 9 or 11, wherein said metallic conductive composition comprises Au.
- 14. The method of forming a green tape by casting a layer of the thick film composition of and one of Claims 2, 3, or 7 onto a flexible substrate and heating the cast layer to remove the volatile organic solvent therefrom.
- 15. A method of forming a green tape by casting a thin layer of the dispersion of any one of Claims 2, 3, or 7 onto a flexible substrate, heating the cast layer to remove the volatile organic solvent therefrom and separating the solvent-free layer from the substrate.
- 16. A method of forming a multilayer interconnection comprising 35 the steps of:
  - (a) forming a patterned array of vias in a plurality of layers of green tape made by the process of Claim 15;

## **EL0515 US NA**

5

10

- (b) filling said vias in the green tape layer(s) of step (a) with a thick film conductor composition;
- (c) printing at least one patterned thick film functional layer over a surface of each of the via-filled green tape layers of step (b)'
- (d) laminating the printed green tape layers of step (c) to form an assemblage comprising a plurality of interconnected functional layers separated by unfired green tape; and
- (e) cofiring the assemblage of step (d).
- 17. The green tape formed by the method of any one of Claims 14 or 15.
- 15 18. The multilayer interconnection formed by the method of Claim 16.